

1                   What is claimed is:

2    **[01]** An architecture for the measurement of photomask optical path difference, comprising:  
3                   A spatially coherent light source;  
4                   An interferometric beam processing module;  
5                   An optical microscope; and  
6                   A photosensitive detector;  
7                   Wherein said module is disposed to receive and divide light from said light source into a  
8                   number of phase-coherent light beams, each of which passes through a separate  
9                   aperture;  
10                  Wherein said microscope is disposed to image the multitude of said apertures in said  
11                  module with a given demagnification onto a photomask; and  
12                  Wherein said detector is disposed to record transmitted fringe intensity.

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14    **[02]** The apparatus of claim 1 wherein said light source is a laser with a wavelength that is  
15                  approximately the same as the actinic wavelength of said photomask.

16    **[03]** The apparatus of claim 1 wherein said optical demagnification of said apertures is greater  
17                  than 50.

18    **[04]** The apparatus of claim 1 wherein said module is of the Mach-Zehnder (MZ)  
19                  interferometer type.

20    **[05]** The apparatus of claim 1 wherein the relative optical phase between said phase-coherent  
21                  light beams may be varied by suitable adjustments to said interferometric beam module.

22    **[06]** The apparatus of claim 1 wherein said module is a dual-aperture screen.

1    [07] The apparatus of claim 1 wherein said module contains mirrors are fabricated using the  
2    techniques of micro-electrical and mechanical system (MEMS).

3    [08] The apparatus of claim 1 wherein said detector is a UV-sensitive CCD camera.

4    [09] The apparatus of claim 1 wherein said detector is a photomultiplier tube (PMT).

5    [10] The apparatus of claim 1 wherein the number of said apertures and said phase-coherent  
6    light beams is two (2).

7    [11] An architecture for the measurement of photomask optical path difference, comprising:  
8        A spatially coherent light source;  
9        An interferometric beam processing module;  
10      An optical microscope; and  
11      A photosensitive detector;  
12      Wherein said module is disposed to receive and divide the light from said light source  
13            into a number of phase-coherent light beams, each of which passes through a  
14            separate aperture;  
15      Wherein said microscope is disposed to image the multitude of said apertures in said  
16            module with a given demagnification onto a photomask; and  
17      Wherein said detector is disposed to record reflected fringe intensity

18    [12] The apparatus of claim 11 wherein said light source is a laser with a wavelength that is  
19    approximately the same as the actinic wavelength of said photomask.

20    [13] The apparatus of claim 11 wherein said optical demagnification of said apertures is  
21    greater than 50.

22    [14] The apparatus of claim 11 wherein said module is of the Mach-Zehnder (MZ)  
23    interferometer type.

1    [15] The apparatus of claim 11 wherein the relative optical phase between said phase-coherent  
2    light beams may be varied by suitable adjustments to said interferometric beam module.

3    [16] The apparatus of claim 11 wherein said module is a dual-aperture screen.

4    [17] The apparatus of claim 11 wherein said module contains mirrors are fabricated using the  
5    techniques of micro-electrical and mechanical system (MEMS).

6    [18] The apparatus of claim 11 wherein said detector is a UV-sensitive CCD camera.

7    [19] The apparatus of claim 11 wherein said detector is a photomultiplier tube (PMT).

8    [20] The apparatus of claim 11 wherein the number of said apertures and said phase-coherent  
9    light beams is two (2).

10